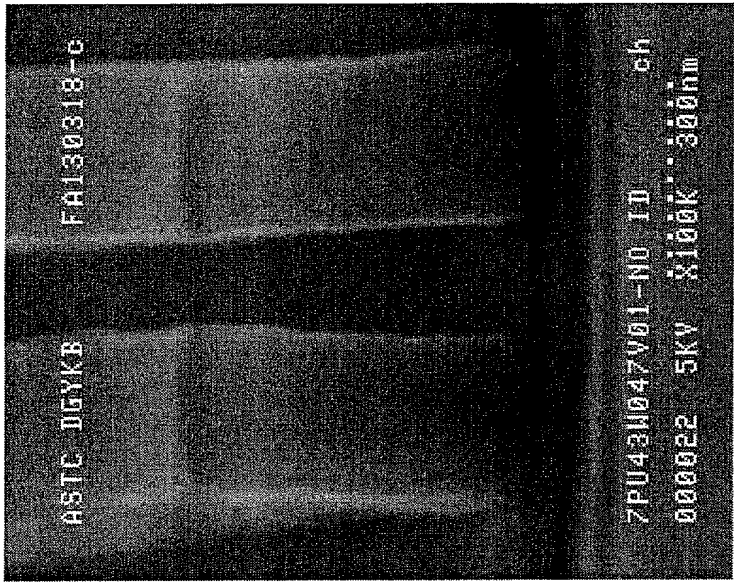
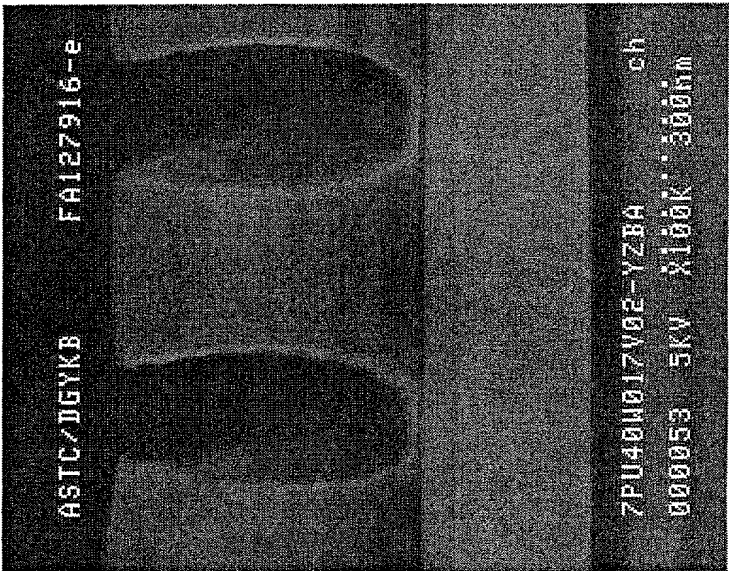


Figure 1



SiCOH low k dielectric film formed from 3MS and non-nitrogen containing oxidant



SiCOH low k dielectric film formed from 3MS and N<sub>2</sub>O oxidant

Figure 2

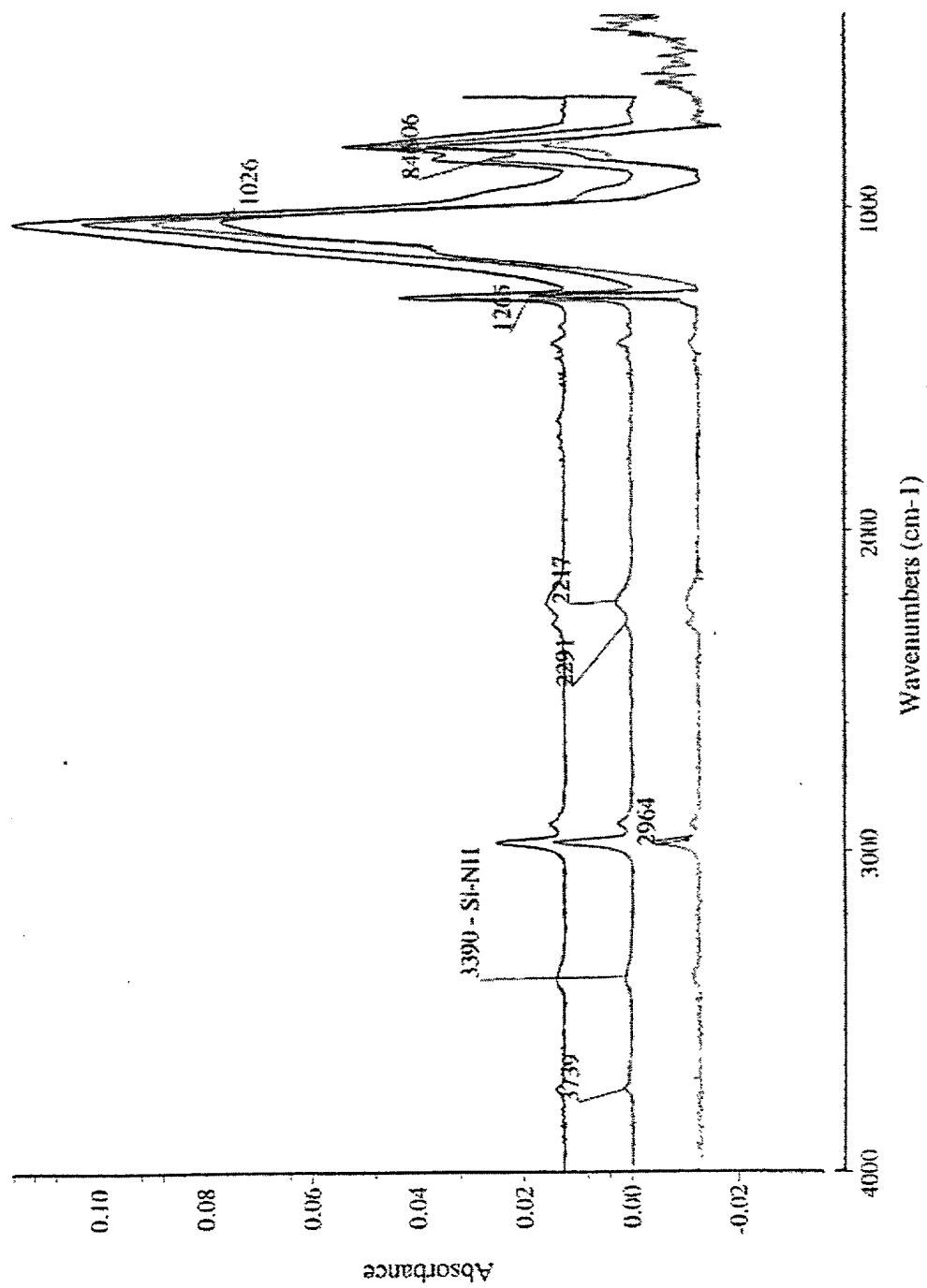


Figure 3

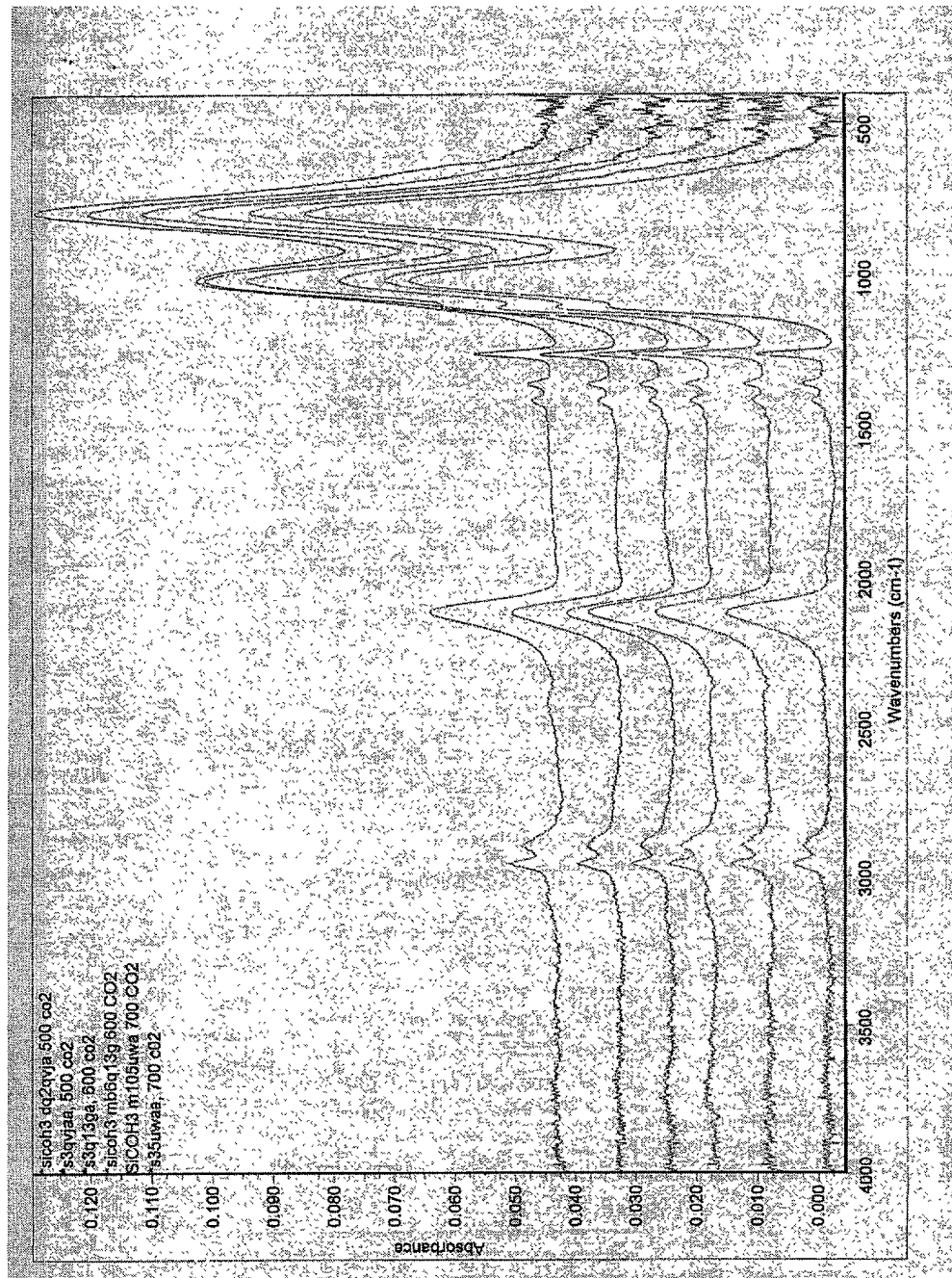


Figure 4